

Search Notes

Application No.

10/720,851

Examiner

Stephen W. Smoot

Applicant(s)

UESAWA, FUMIKATSU

Art Unit

2813

SEARCHED

Class	Subclass	Date	Examiner
438	620	6/25/2004	SWS
438	637	6/25/2004	SWS
438	640	6/25/2004	SWS
438	669	6/25/2004	SWS
438	671	6/25/2004	SWS
438	673	6/25/2004	SWS
438	780	6/25/2004	SWS

*S.W.S.***INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: Mask - Organic, Tapered, Photoresist, Resist, Aperture, Hole Opening;	6/25/2004	<i>S.W.S.</i> SWS
Dual Hard Mask; Low Temperature Etching.	6/25/2004	<i>S.W.S.</i> SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	6/25/2004	<i>S.W.S.</i> SWS